

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1662	(438/689,700,712).CCLS.	USPAT	OR	OFF	2005/07/14 15:37

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Search Results -

Terms	Documents
damascene and ((plasma adj etch\$) same CO) and ((photoresist or resist) same harden\$ or resist\$)	0

Database:

US Pre-Grant Publication Full-Text Database
 US Patents Full-Text Database
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 Derwent World Patents Index
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L6

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DATE: Thursday, July 14, 2005 [Printable Copy](#) [Create Case](#)

<u>Set</u> <u>Name</u> side by side	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
	<i>DB=JPAB; PLUR=YES; OP=ADJ</i>		
<u>L6</u>	damascene and ((plasma adj etch\$) same CO) and ((photoresist or resist) same harden\$ or resist\$)	0	<u>L6</u>
	<i>DB=EPAB; PLUR=YES; OP=ADJ</i>		
<u>L5</u>	damascene and ((plasma adj etch\$) same CO) and ((photoresist or resist) same harden\$ or resist\$)	0	<u>L5</u>
	<i>DB=USPT; PLUR=YES; OP=ADJ</i>		
<u>L4</u>	damascene and ((plasma adj etch\$) same CO) and ((photoresist or resist) same harden\$ or resist\$)	54	<u>L4</u>
	<i>DB=PGPB; PLUR=YES; OP=ADJ</i>		
<u>L3</u>	damascene and ((plasma adj etch\$) same CO) and ((photoresist or resist) same harden\$ or resist\$)	58	<u>L3</u>
	<i>DB=TDBD; PLUR=YES; OP=ADJ</i>		
<u>L2</u>	damascene and ((plasma adj etch\$) same CO) and ((photoresist or resist) same harden\$ or resist\$)	0	<u>L2</u>
	<i>DB=DWPI; PLUR=YES; OP=ADJ</i>		

L1 damascene and ((plasma adj etch\$) same CO) and ((photoresist or resist)
same harden\$ or resist\$)

3 L1

END OF SEARCH HISTORY